

In the Claims:

Please rewrite Claim 5 as follows:

5. (Amended) The plasma treatment equipment according to claim [3] 4, wherein the said metal plate is inclined with respect to the bottom wall, and an angle formed between said metal plate and the bottom wall is less than 45 degrees.

Please add new Claims 13-23 as follows:

13. (New) Plasma treatment equipment comprising:
a chamber wall; and
a susceptor electrode having at least one of an electrode and an electrode shield, at least one of the electrode and the electrode shield being at the same DC potential as the chamber wall,
wherein at least one of the at least one of the electrode and the electrode shield being at the same DC potential as the chamber wall is AC shorted to the chamber wall.

14. (New) The plasma treatment equipment according to claim 13, wherein the at least one of the electrode and the electrode shield being at the same DC potential as the chamber wall is the electrode shield.

15. (New) The plasma treatment equipment according to claim 14, wherein said chamber wall and said electrode shield are shorted to each other at a location that is within a distance shorter than 500 mm from a side wall of the chamber wall.

16. (New) The plasma treatment equipment according to claim 15, wherein said electrode shield is shorted to said chamber wall at a short point on a bottom wall of the chamber wall, said short point being located within a distance shorter than 500 mm from a side wall of the chamber wall as measured along the bottom wall.

17. (New) The plasma treatment equipment according to claim 14, wherein said chamber wall and said electrode shield are shorted at a plurality of short points.

18. (New) The plasma treatment equipment according to claim 17, wherein the plurality of short points are disposed approximately symmetrically with respect to a center of said electrode shield.

19. (New) The plasma treatment equipment according to claim 14, wherein said electrode shield is shorted to a side wall of the chamber wall.

20. (New) The plasma treatment equipment according to claim 16, wherein said electrode shield is shorted to said chamber wall by a metal plate, said metal plate being connected between the short point on the bottom wall and a second short point on the electrode shield.

21. (New) The plasma treatment equipment according to claim 20, wherein said metal plate is inclined with respect to the bottom wall, and an angle formed between said metal plate and the bottom wall is less than 45 degrees.

22. (New) The plasma treatment equipment according to claim 13, wherein the at least one of the electrode and the electrode shield being at the same DC potential as the chamber wall is the electrode, the electrode being shorted to the chamber wall by a metal plate.

23. (New) Plasma treatment equipment comprising:
a plasma chamber having a wall; and
a susceptor electrode disposed within the plasma chamber, said susceptor electrode comprising at least one of an electrode and an electrode shield, the electrode shield disposed adjacent to said electrode, wherein the wall of the plasma chamber and at least one of the electrode and the electrode shield have the same DC potential, and
wherein the wall of the plasma chamber and the electrode shield are AC shorted to each other.